



- 4 3
- 5
- 6
- 6a
- 6b
- 7a 7b 200mm
- 8a 8b 300mm
- 9a 200mm
- 9b 300mm

(edge) 가 (baking)

(photolithography) (photoresist)

(shear stress) 가 (hot plate)

가

가

1 가 가 가 ( )

가 W 가 W 가 (1) W가 (1)

가 가 (3) 가 (2) W가 (1) (3) 가 (5)

가 (4) (5) (1) (1) (1)

가 (1) (3) W , 100 200um 가 (3a)

가 ( ) W (4) (5)가 (1) W (5)가 (3)

가 (4) (1) (5) (2) W (1) 가 (1)

W가 (1) (5) (4) W (1) W

가 (1) W , 가 W , 가

W 가 W , 2 W , 가 W , 가

W , W , W , 가

가

가

, 가

가

,

10) (10) 3 (10) , W 가 (10) ; ( (10) )  
 (20) W (20) ; W가 (20) 가  
 (30) ; (30) W (10) (30a)  
 40) ; 가 (50) (10) (10) (40) (50) ; ( (40) )  
 1) (40) (41) (60) 가 (60) W (4) (40) W  
 (30) (40) W W  
 (41) 5 가 3  
 5 (46) (45) (46) (60) 가 W W  
 W (45) (46) W 가  
 3 5 (40,45) (20) (30)  
 (40,45) (30) (30a) W  
 가 (42,47)가 , 가 (42,47) W ( (42,47) )  
 ) 가 (42,47) / (50) (60) (40,45)가 (3  
 0) (30a) 가 (30) W (10) (20) W가 W (30a) (30)  
 W가 W (20) (50) (60) (40,45)가  
 W (10) 가 (40,45) W (30) (20)  
 (10) 가 , 가 (42,47) (40,45) 가 (42,47) W  
 , 4 (40,45) W 가 (42,47) W W 가  
 W (40,45) W (10) 가 (40,45) 가  
 W가 W (60) (40,45) (50)  
 , 5 (45) 3 (40) W  
 W (45) 가 (47)  
 W 3 6a (40)  
 (41) W  
 W 5 6b (45)  
 (46) W 가 W 가 W W

W (40,45) 가 (10) (42,47) W (10) W  
 7a 7b, 9a < 1> 가  
 7a 7b < 1> 200mm 가

[ 1 ]

	T <sub>max</sub>	T <sub>min</sub>	T <sub>max</sub>	T <sub>min</sub>
200mm	299.32	296.87	300.95	300.09
T(T <sub>max</sub> - T <sub>min</sub> )	2.45		0.86	
	100%		35%	

7a 7b < 1> , 200mm  
 (T<sub>max</sub>) 299.32 , (T<sub>min</sub>) 296.87  
 (T) 2.45  
 ax) 300.95 , (T<sub>min</sub>) 300.09 , (T) 0.86 (T<sub>m</sub>  
 100%  
 35% , 가  
 300mm 가 , 8a 8b 9b 200mm 가  
 , < 2>

[ 2 ]

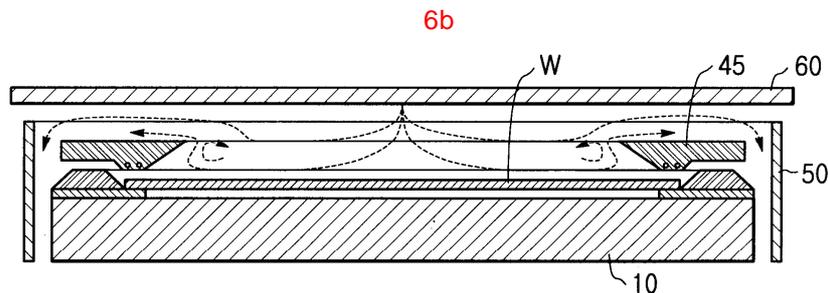
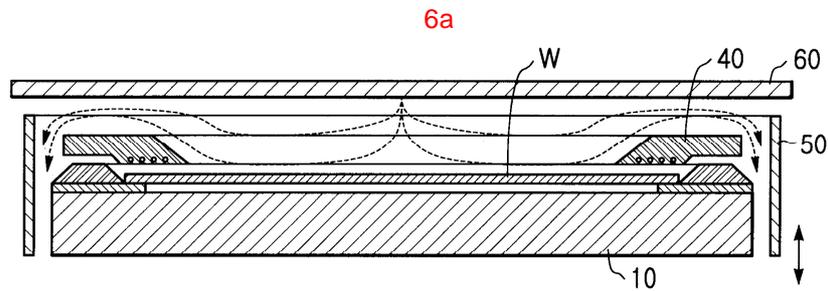
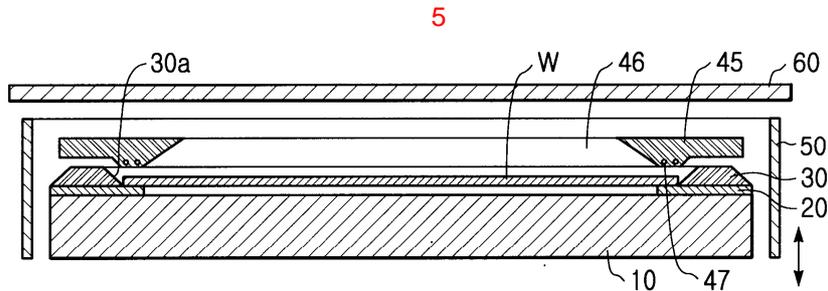
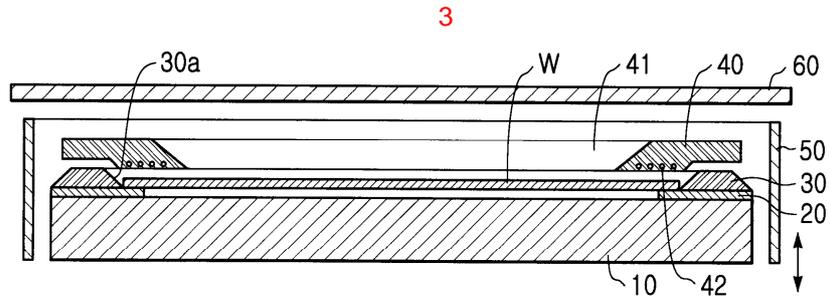
	T <sub>max</sub>	T <sub>min</sub>	T <sub>max</sub>	T <sub>min</sub>
300mm	300.96	296.13	302.23	300.23
T(T <sub>max</sub> - T <sub>min</sub> )	4.83		2.00	
	100%		41%	

8a 8b < 2> , 300mm  
 (T<sub>max</sub>) 300.96 , (T<sub>min</sub>) 296.13  
 (T) 4.83  
 ax) 302.23 , (T<sub>min</sub>) 300.23 , (T) 2.00 (T<sub>m</sub>  
 100%  
 41% , 가

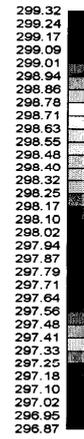
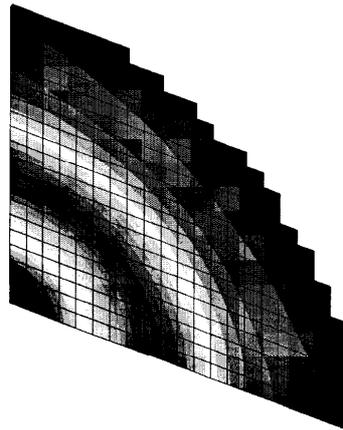
가  
 가

가 가

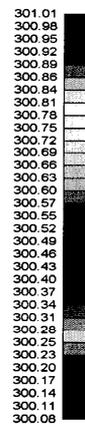
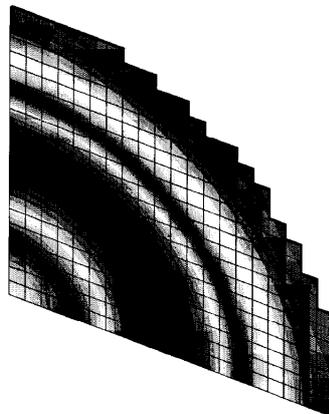




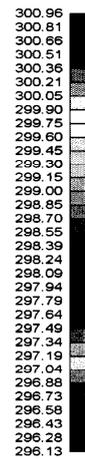
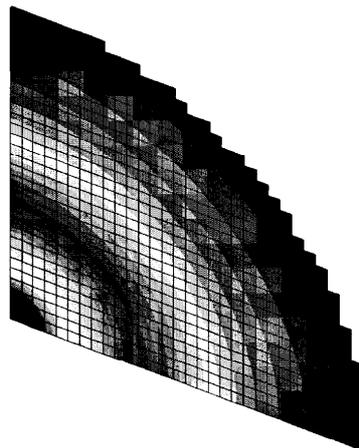
7a



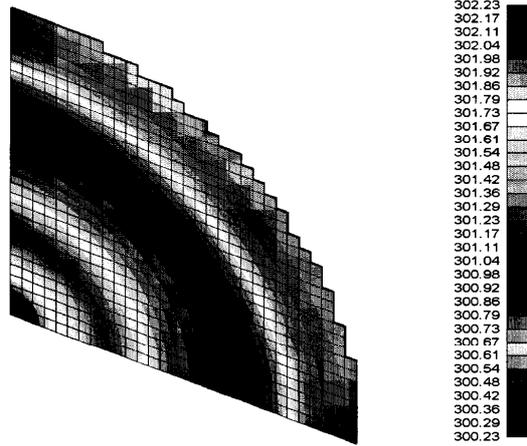
7b



8a

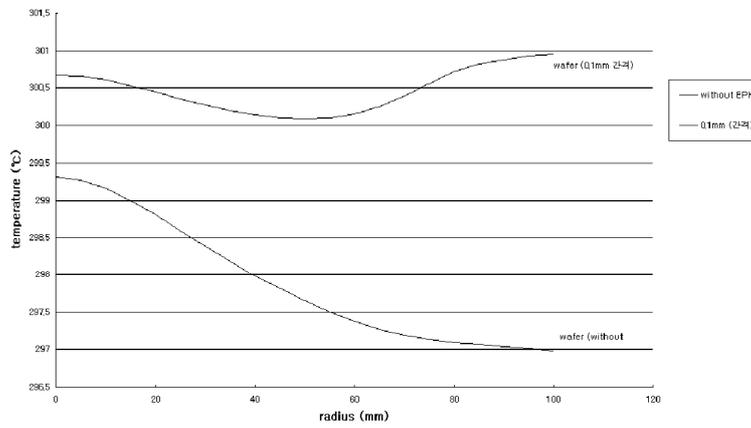


8b



9a

200mm wafer 표면에서의 온도 분포



9b

300mm wafer 표면에서의 온도 분포

